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(54) **SUBSTRATE PROCESSING APPARATUS**

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(57) **ABSTRACT**

A substrate processing apparatus includes a processing unit including a processing vessel with an internal space and a support unit configured to support a substrate and rotate the substrate in a first rotation direction in the internal space, and an exhaust unit configured to exhaust a gas from the internal space, wherein the exhaust unit includes an exhaust pipe providing an exhaust path for the gas exhausted from the internal space, and one or more connectors connecting the processing vessel to the exhaust pipe, and one end of the exhaust pipe is closed, and an open outlet is formed at a remaining end of the exhaust pipe to discharge the gas.